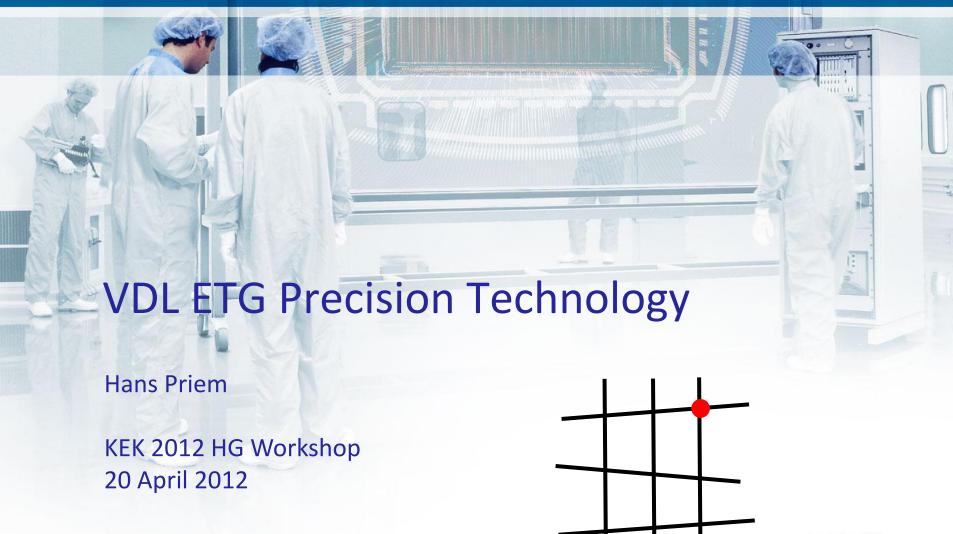
VDL Enabling Technologies Group





- Introduction of VDL ETG
- VDL ETG Core Technology Competences
- Accelerator Technology Trends
- Future Business Requirements
- Commitment to accelerator development

Key Figures VDL ETG

VDL Enabling Technologies Group

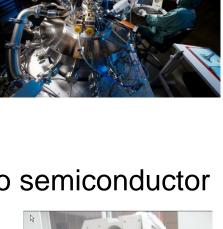
- Subcontracting Business Unit of the VDL Group
- A Privately Owned Business
- > €500M Revenues (VDL total €1,7B)

VDL ETG is a key supplier of complex modules to semiconductor

and analytical equipment manufacturers WW

- Market Drivers
 - Reliability
 - Time to Market
 - Operational Excellence







VDL ETG Combines key strengths in one global operating company

PROCESSES

Design
Engineering
Proto Typing
Built to Print
Sustaining



Products & Services

Manufacturing Engineering
Parts Manufacturing
Module Assembly
System Integration

COMPENTENCIES

Positioning
Handling
Vacuum Technology
Ultra / High Precision
Metrology
Time-to-Market
Operational Excellence



Commitment to accelerator engineering & manufacturing

- Precision technology is a key building block in VDL ETGs company strategy – creating synergy is essential
 - Immediate tangible added value to the accelerator requirements based on our >30 year experience..and..because of this..
 - Spin-off to our main stream businesses in mid / long-term
- One integral process to handle high complexity, secure fast response, and deliver highest quality & reliability
- One dedicated team is responsible for entire process: from RFI to Delivery
 - From design to proto typing to series manufacturing

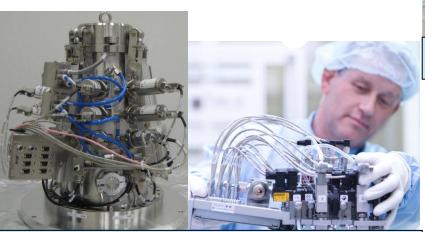
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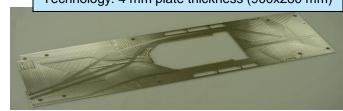
VDL ETG Core Technology Competences

- High Precision (HPT)
- Ultra High Precision (UPT)
- Metrology
- Welding / Vacuum Brazing
- Vacuum Technology



Parts manufacturing, cleaning, and assembly for EUV vacuum applications

Accuracy: 10 µm flat over 900 mm length Shape: Water-cooling and N-purging channels Technology: 4 mm plate thickness (900x280 mm)

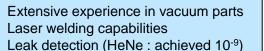






Guide ways for NANO-CMM Accuracy: 0.2 µm straightness over 300 mm



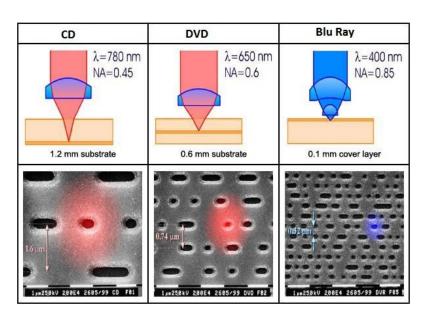




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Continuous challenge to achieve higher accuracy

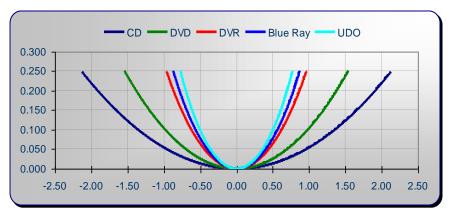


Required accuracy's change:

✓ Form accuracy : 150 nm ⇒ 50 nm

✓ Roughness Ra : 5 nm ⇒ 2 nm

All with higher NA and steeper aspheres Increasing influence of tool setup errors



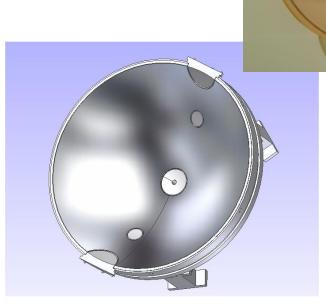
Constant push to improve manufacturing and metrology capabilities (means and equipment) to meet the demands



Tight accuracy specifications for series manufacturing

- Mould for DVD optics :
 - 50 nm form accuracy on Ø 2 mm
 - equals ratio of 1 / 40000
- CLIC disk
 - 2 μm accuracy on Ø 80 mm
 - equals ratio of 1 / 40000
- Collector for EUV light source
 - 5 μm form accuracy on Ø 400 mm
 - equals ratio of 1 / 80000





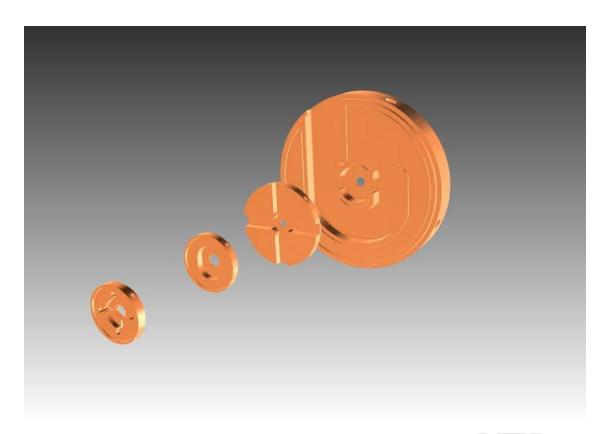


Bigger structures, same tolerances

Diameter increases – accuracy specification remains the same

- 4 μm profile accuracy
- 2 μm on diameters
- 1 μm flatness

- ø 40 DDS
- ø 50 Crab cavity
- ø 80 TD 24
- ø 200 Coupler



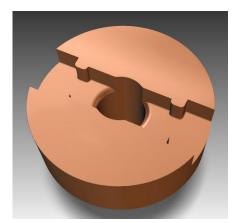


Product specifications will demand special tooling

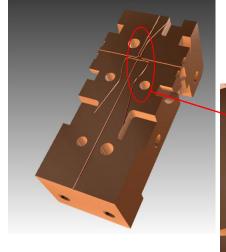
- Free form parts
 - Diamond tools with extreme clearance angles
- RF components for astronomy
 - Small tools (ø 50μm) with large depth of cut (4xd)



- Acceleration structures
 - Long tools with small radii required







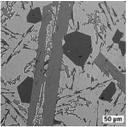


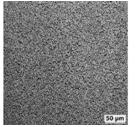
Difficult to machine materials and combinations

- Parts for electron optics
 - Combination of ceramics and copper
- Mirrors for satellites
 - High reflectivity required on aluminum
- Acceleration structures
 - Soft copper is difficult to machine
 - Sensitive to scratches and marks









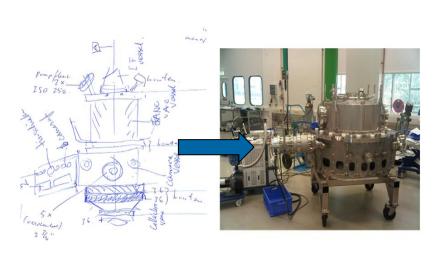


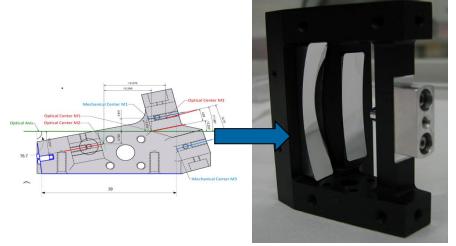
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24-01-2011

Time to Market

- Co-development & rapid proto typing to enable innovation to effectively reach its end-users
 - EUV source vacuum vessel (lithographic process semiconductor production)
 - ESA nano satellite telescope with complex aspherical mirrors

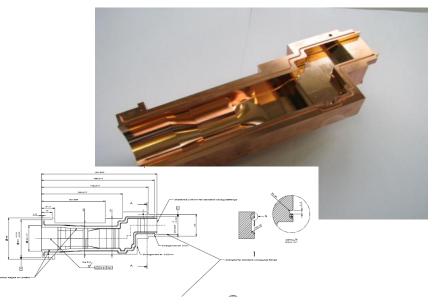




28-01-2012

Industrialization

- Early customer involvement cost control & risk reduction
 - A successful proto typing process results in a design verification
- Co / Redesign for manufacturability
 - Straight mode converter from 16 to 2 parts
 - E-ELT frame and actuators redesigns reduced weight 100kg
 - Pulse compressor reduced cost







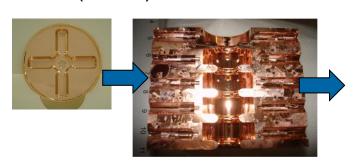
Increased complexity requires higher level outsourcing

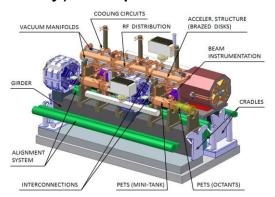
Securing shortest cycle time to end-product

EUV Vacuum Wafer Stage: from magnet table to complete qualified module



CLIC (future): from cell to bonding to (ultimately) complete module





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Industry Commitment Required

- Accelerator development is reaching maturity step by step
 - From conceptual designs and proto typing towards industrialization
- Manufacturing process experience & knowledge is essential
 - secure time to market, cost control / reduction, yield, and quality
- Capital investments are increasing significantly
 - High mutual commitment between industry and institutes is essential
 - Alignment is required now to meet time to market

	2010				Т	2011				20	012			2013				2014					2015				2016			
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CTF3 TBTS operation	inst 1-2 structures, beam loading, breakdown kick												110-7		dien i	Vic-						7.			1.07					
CTF3 TBL operation	ins	Deceler ation 8 inst. PETS				final decelerato test (16 PETS, 50%)											-													
Modules lab	ins	tali	l tes latio dule	n 2		further tests, installation 4 modules				testing							pre-series production, industrialization													
Modules CTF3								1110	1 dule st.		ting 1 dule		3 dule nst.		te	stin	g 3 m	odu	les					> 4	pg	rad	es?			
CTF3 phase feedback	design, hardware tests						is.		tallat																					
CTF3 TBL+										flat commis n sio-ning							RFt	RF testing, potential upgrades												
CLIC DB injector & Jinac	design & hardware construction							tion	Installation commissioning							staged upgrade & testing														
RF structures									tures built, establish precision RN or elsewhere, 5 µm tolerances achieved								more than 200 structures built, final cost optimization, pre-series with industry													
RF test									continue testing with increased capabilities, CERN or elsewhere.								estin	g, u	o to	200	acce	eler:	ating	st	ruct	ure	rs plu	us		
infrastructure	inst. two slots)					-	up to 10 slots								PETS and RF components															
Prototypes of critical components	technical choices, design						0	construction, hardware tests								finalization, performance & cost optimization, industrialization for large scale components														

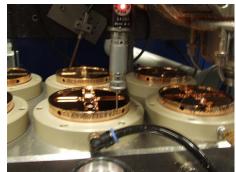




VDL ETG Industry Commitment

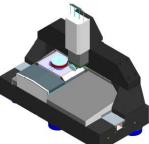
- Investments in new skills
 - H2 bonding
 - Micro milling
 - Pallet machining
 - On machine metrology





- Investments in people
 - Cooperation programs with schools, universities, institutes
 - Internal education
 - Career paths
- Investments in infrastructure
 - Equipment
 - New Facility







• Guidance is required to steer investments in the right direction

VDL ETG Industry Commitment

By combining technological competences and extensive experience in industrialization of complex modules, VDL ETG enables you to successfully steer accelerator technology towards maturity

Accelerators are essential to future applications

We will enable your ambitions